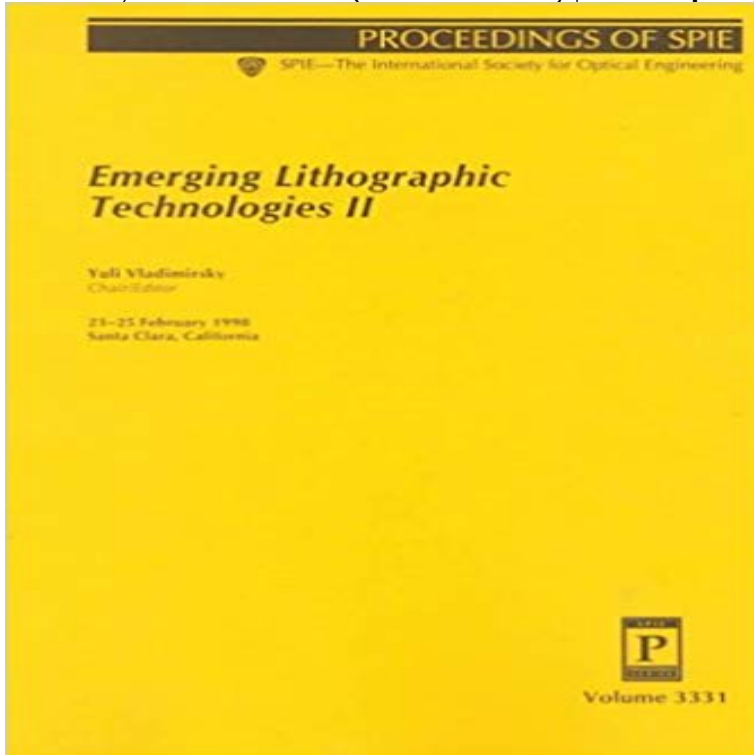


# Emerging Lithographic Technologies II: 23-25 February 1998 Santa Clara, California (Proceedings of Spie, Volume 3331)



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